

Inventor: Luan C. Tran  
Title: Methods of Forming Semiconductor Constructions  
Assignee: Micron Technology, Inc.

**INFORMATION DISCLOSURE STATEMENT**

**PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98**

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional application of co-pending application Serial No. 10/364,054, filed February 10, 2003. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated:

*July 21, 2003*

By:

*Jennifer J. Taylor*  
Jennifer J. Taylor, Ph.D.  
Reg. No. 48,711

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2356	priority SERIAL NO. 10/364,054	
<b>LIST OF ART CITED BY APPLICANT</b> (Use several sheets if necessary)				APPLICANT Luan C. Tran		
				priority FILING DATE February 10, 2003	priority GROUP 2812	
<b>U.S. PATENT DOCUMENTS</b>						
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,458,666 B2	10-2002	Wasshuber		
	AB	6,444,548 B2	09-2002	Divakaruni et al.		
	AC	3,886,003	05-1975	Takagi et al.		
	AD	4,366,338	12-1982	Turner et al.		
	AE	6,008,115	12-1999	Jung		
	AF	6,506,647 B2	01-2003	Kuroda et al.		
	AG	US2001/0036713A1	11-01-2001	Rodder et al.		July 5, 2001
	AH	US2002/0034865A1	03-21-2002	Umimoto et al.		Nov. 30, 2001
	AI	09/876,722		Scott		June 6, 2001
	AJ	10/133,193		McQueen et al.		April 26, 2002
	AK					
	AL					
<b>FOREIGN PATENT DOCUMENTS</b>						
	Document Number	Date	Country	Class	Subclass	Translation
						Yes    No
	AM					
	AN					
	AO					
	AP					
<b>OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)</b>						
	AQ		Young et al., "A 0.13 $\mu$ m CMOS Technology with 193 nm Lithography and Cu/Low-k for High Performance Applications", IEDM, pgs. 563-566, April 2000.			
	AR		Yeh et al., "Optimum Halo Structure for Sub-0.1 $\mu$ m CMOSFETs", IEEE Transactions on Electronic Devices, Vol. 48, No. 10, October 2001, pgs. 2357-2362.			
	AS		Bouillon et al., "Re-examination of Indium implantation for a low power 0.1 $\mu$ m technology", IDEM, pgs. 897-900, 1995 (year is sufficient so that date is not in issue).			
<b>EXAMINER</b>			<b>DATE CONSIDERED</b>			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						